



## Thin Film Deposition: From Fundamental Research to Applications

Guest Editors:

**Prof. Dr. José Guadalupe  
Quiñones-Galván**

Departamento de Física, Centro  
Universitario de Ciencias Exactas  
e Ingenierías, Universidad de  
Guadalajara, Blvd. Marcelino  
García Barragán 1421,  
Guadalajara JAL 44430, Mexico

**Dr. Laura Patricia Rivera  
Reséndiz**

Departamento de Física, Centro  
Universitario de Ciencias Exactas  
e Ingenierías, Universidad de  
Guadalajara, Blvd. Marcelino  
García Barragán 1421,  
Guadalajara JAL 44430, Mexico

Deadline for manuscript  
submissions:

**closed (31 January 2024)**

### Message from the Guest Editors

Dear Colleagues,

Development in thin film deposition technologies has allowed the accelerated increase in almost all areas of science and technology we see today. The increasing demand for miniaturized devices and nanotechnology has motivated researchers to find new ways to synthesize or improve all kinds of thin film material systems using many physical and chemical thin film deposition techniques. This Special Issue is focused on publishing scientific research papers and review articles that discuss fundamental thin film research:

- Synthesis techniques: novel studies on thin film deposition techniques, such as advances in pulsed laser deposition, sputtering, chemical vapor deposition, and sol–gel, among others;
- Characterization: study of physical and chemical properties of different types of thin film materials;
- Applications: Experiments applying thin films in different fields of science;
- Simulation and theoretical calculations: studies on theory or simulation around specific properties or applications of thin films.

Prof. Dr. José Guadalupe Quiñones-Galván  
Dr. Laura Patricia Rivera Reséndiz  
*Guest Editors*





## Editor-in-Chief

## Message from the Editor-in-Chief

You are invited to contribute research articles or comprehensive reviews for consideration and publication in *Micromachines* (ISSN 2072-666X). *Micromachines* is published in the open access format. Research articles, reviews and other contents are released on the internet immediately after acceptance. The scientific community and the general public have unlimited free access to the content as soon as it is published. As an open access journal, *Micromachines* is supported by the authors or their institutes by payment of article processing charges (APC) for accepted papers. We are pleased to welcome you as our authors.

## Author Benefits

**Open Access:** free for readers, with article processing charges (APC) paid by authors or their institutions.

**High Visibility:** indexed within Scopus, SCIE (Web of Science), PubMed, PMC, Ei Compendex, dblp, and other databases.

**Journal Rank:** JCR - Q2 (*Chemistry, Analytical*) / CiteScore - Q2 (*Mechanical Engineering*)

## Contact Us

*Micromachines* Editorial Office  
MDPI, St. Alban-Anlage 66  
4052 Basel, Switzerland

Tel: +41 61 683 77 34  
[www.mdpi.com](http://www.mdpi.com)

[mdpi.com/journal/micromachines](http://mdpi.com/journal/micromachines)  
[micromachines@mdpi.com](mailto:micromachines@mdpi.com)  
[X@micromach\\_mdpi](https://x.com/micromach_mdpi)